

**FASH 62A Course Outline as of Fall 2013****CATALOG INFORMATION**

Dept and Nbr: FASH 62A Title: FLAT PATTERN DESIGN 1

Full Title: Flat Pattern Design 1

Last Reviewed: 2/24/2020

Units	Course Hours per Week		Nbr of Weeks		Course Hours Total	
Maximum	2.00	Lecture Scheduled	1.50	17.5	Lecture Scheduled	26.25
Minimum	2.00	Lab Scheduled	1.50	6	Lab Scheduled	26.25
		Contact DHR	0		Contact DHR	0
		Contact Total	3.00		Contact Total	52.50
		Non-contact DHR	0		Non-contact DHR	0

Total Out of Class Hours: 52.50

Total Student Learning Hours: 105.00

Title 5 Category: AA Degree Applicable

Grading: Grade or P/NP

Repeatability: 00 - Two Repeats if Grade was D, F, NC, or NP

Also Listed As:

Formerly: CLTX 50A

**Catalog Description:**

The student will learn basic patternmaking skills using the Flat Pattern Method. A basic fitting pattern is developed and used to create patterns for original, individual designs. Patterns for skirts, pants, tops, dresses, sleeves, collars, and knits are discussed. Construction of a garment from an original design and pattern required.

**Prerequisites/Corequisites:****Recommended Preparation:**

Course Completion or Concurrent Enrollment in FASH 70A

**Limits on Enrollment:****Schedule of Classes Information:**

Description: The student will learn basic patternmaking skills using the Flat Pattern Method. A basic fitting pattern is developed and used to create patterns for original, individual designs. Patterns for skirts, pants, tops, dresses, sleeves, collars, and knits are discussed. Construction of a garment from an original design and pattern required. (Grade or P/NP)

Prerequisites/Corequisites:

Recommended: Course Completion or Concurrent Enrollment in FASH 70A

Limits on Enrollment:

Transfer Credit: CSU;

Repeatability: Two Repeats if Grade was D, F, NC, or NP

## **ARTICULATION, MAJOR, and CERTIFICATION INFORMATION:**

**AS Degree:** Area Effective: Inactive:

**CSU GE:** Transfer Area Effective: Inactive:

**IGETC:** Transfer Area Effective: Inactive:

**CSU Transfer:** Transferable Effective: Fall 1987 Inactive:

**UC Transfer:** Effective: Inactive:

**CID:**

**Certificate/Major Applicable:**

Both Certificate and Major Applicable

## **COURSE CONTENT**

**Outcomes and Objectives:**

Upon completion of the course, students will be able to:

1. Apply the basic skills of flat pattern making to interpret a garment design and successfully translate it into a paper pattern and a final, completed garment.
2. Compare body measurements to pattern pieces in order to make necessary alterations for a proper fit, for themselves or for others.
3. Create a basic sloper used for pattern design which will fit their personal body proportions.
4. Interpret three-dimensional garment designs into two-dimensional "flat" pattern pieces.
5. Manipulate the basic sloper pattern to create patterns for various parts of a garment, including, but not limited to: bodices, skirts, pants, sleeves, collars, and dresses.
6. Create a final pattern with accurate markings, including grainlines and seam allowances, which could be used and understood by others.
7. Demonstrate the above processes by designing 2 full-scale garments from their personal sloper and completing one garment in fashion fabric.
8. Research some ways in which computers are used in flat pattern development in the fashion industry.
9. Based on subsequent repeats, students will be able to apply techniques to:
  - a. increasingly complex applications
  - b. increasingly complex patterns
  - c. fabric manipulation with a variety of fabric textures
  - d. increasingly complex fitting issues and adjustments
  - e. gain confidence and speed

**Topics and Scope:**

- I. Measurements for Proper Fitting
- II. Alterations of Basic Pattern
- III. Fitting and Final Adjustments of Basic Fitting Shell

- IV. Interpreting 3-D Design into Flat Pattern Pieces
- V. Creation and Use of Basic Cardboard Sloper from Fitted Shell
- VI. Using Sloper to Create Basic Designs:
  - A. Bodices
  - B. Skirts and pants
  - C. Dresses
  - D. Sleeves
  - E. Collars
  - F. Coats and jackets
- VII. Flat Pattern Techniques for Personal and Industry Use
- VIII. Basic Demonstration of Computer Use for Flat Pattern Design
- IX. Repeating students will be receive advanced techniques and more complex concepts.

**Assignment:**

1. Practice pattern designs in 1/4" or 1/2" scale (6-half scale; 1-sloper/foundation; 1-final full scale pattern fashion garment)
2. Complete a fitting shell and personal cardboard sloper
3. Complete 2 garment designs including 2 full scale paper patterns with complete and accurate markings
4. Create a garment in fabric using one of the 2 patterns
5. Read from text; 5 to 15 pages per week
6. Quizzes (2 to 3), mid-term
7. Repeating students will be expected to produce more complex projects

**Methods of Evaluation/Basis of Grade:**

**Writing:** Assessment tools that demonstrate writing skills and/or require students to select, organize and explain ideas in writing.

None, This is a degree applicable course but assessment tools based on writing are not included because problem solving assessments and skill demonstrations are more appropriate for this course.

Writing  
0 - 0%

**Problem Solving:** Assessment tools, other than exams, that demonstrate competence in computational or non-computational problem solving skills.

Homework problems: practice pattern design

Problem solving  
10 - 30%

**Skill Demonstrations:** All skill-based and physical demonstrations used for assessment purposes including skill performance exams.

Fitting shell and cardboard sloper, full-scale garments with patterns, final garment in fabric

Skill Demonstrations  
50 - 70%

**Exams:** All forms of formal testing, other than skill performance exams.

Exams: multiple choice, true false, matching, completion, short essay

Exams  
10 - 20%

**Other:** Includes any assessment tools that do not logically fit into the above categories.

Attendance and participation

Other Category  
10 - 20%

**Representative Textbooks and Materials:**

Patternmaking for Fashion Design, Helen J. Armstrong, 5th Edition, Prentice-Hall 2009.